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ABSTRACT

5 An electromagnetic field generating coil included in
plasma processing apparatus is realized with a balanced
transmission line. Conductors constituting the balanced
transmission line are disposed vertically above a wafer.
A uniform electromagnetic field is generated in parallel
with the wafer using the balanced transmission line. A
gas inlet is formed above the balanced transmission line
10 so that a gas will flow into the wafer after passing
through the electromagnetic field generated around the
balanced transmission line. The balanced transmission
line may be formed spirally.